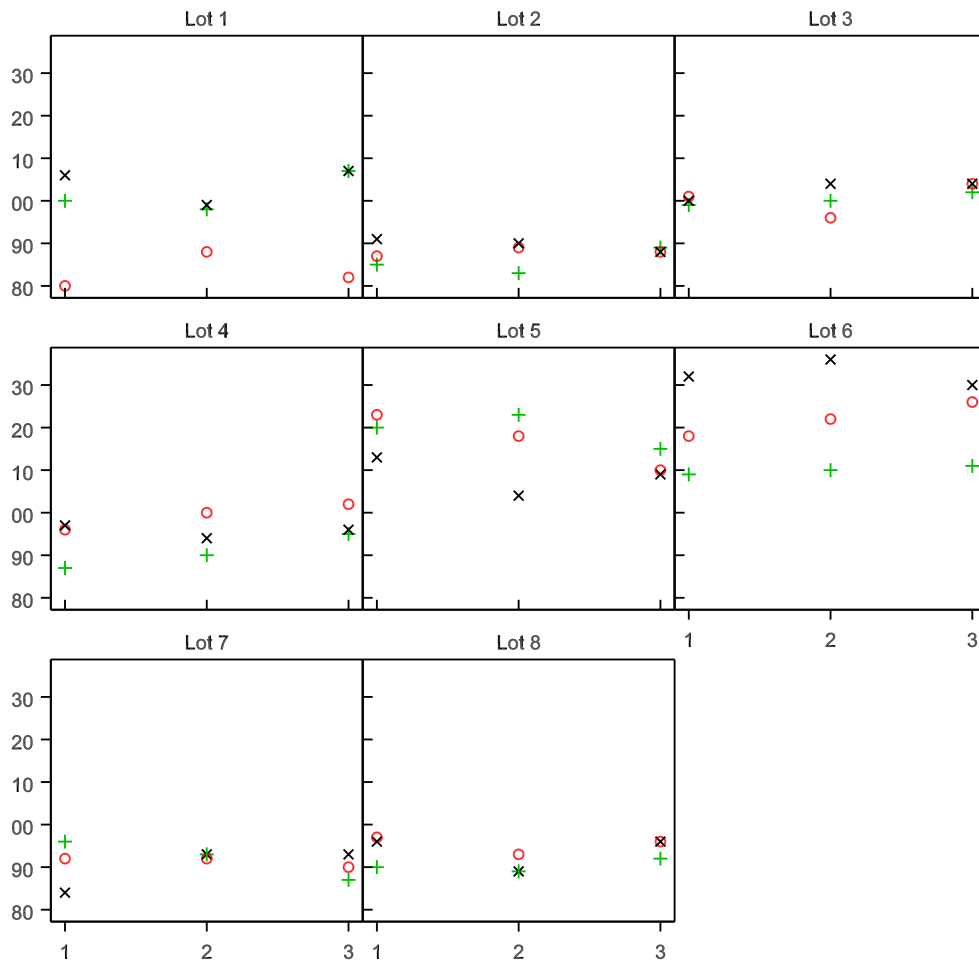


GenStat test

We will analyze a dataset with 72 observations discussed in Littel *et. al*, *SAS System for Mixed Models*. Ee have 72 observations of oxide thickness in a semiconductor manufacturing process. We run 4 lots with each of two suppliers, with three wafers per lot. Oxide thickness is then measured at three sites.

Here is a glance at the data for each lot:

```
GS> TRELLIS [GROUPS=Lot; PENGROUP=Wafer; FIRSTPICTURE=top] \
GS> Y=Thickness; X=Site; METHOD=Point
```



Here is an analysis based on the multi-stratum error structure that GenStat is famous for.

```
GS> BLOCK Lot/Wafer
GS> TREATMENTS Source*Site
GS> ANOVA [PRINT=aovtable,information,means; FPROB=yes; PSE=diff] Thickness
```

47.....

Analysis of variance

=====

Variate: Thickness

Source of variation	d.f.	s.s.	m.s.	v.r.	F pr.
---------------------	------	------	------	------	-------

Lot stratum					
Source	1	1830.12	1830.12	1.53	0.263
Residual	6	7195.19	1199.20	9.98	
Lot.Wafer stratum					
	16	1922.67	120.17	9.98	
Lot.Wafer.*Units* stratum					
Site	2	15.44	7.72	0.64	0.531
Source.Site	2	58.33	29.17	2.42	0.100
Residual	44	529.56	12.04		
Total					
	71	11551.32			

* MESSAGE: the following units have large residuals.

Lot 1	Wafer 2	-13.00	s.e. 5.17
Lot 6	Wafer 1	11.11	s.e. 5.17
Lot 6	Wafer 3	-11.56	s.e. 5.17
Lot 5	Wafer 2	*units* 3	-6.39 s.e. 2.71
Lot 7	Wafer 1	*units* 1	-6.64 s.e. 2.71

Tables of means
=====

Variate: Thickness

Grand mean 2000.15

Source	1	2		
	1995.11	2005.19		
Site	1	2	3	
	1999.96	1999.71	2000.79	
Source	Site	1	2	3
1		1994.08	1994.25	1997.00
2		2005.83	2005.17	2004.58

Standard errors of differences of means

Table	Source	Site	Source
			Site
rep.	36	24	12
s.e.d.	8.162	1.001	8.244
d.f.	6	44	6.24
Except when comparing means with the same level(s) of			
Source			1.416
d.f.			44